Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S17	436	semiconductor and ((mask$4) with (amorphous and carbon))	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/01/18 16:42
S18	28	semiconductor and ((mask$4) with (amorphous and carbon)) and damascene and (CMP or (mechanical near3 polish$4)) and (ARC or anti-reflect$5 or antireflect$5 or anti adj reflect$5)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/18 19:29
S19	56	(257/758 or 257/760).ccls. and (amorphous same mask$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/01/18 19:30
S20	351	(257/758 or 257/760 or 438/671). ccls. and (amorphous) and (mask$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/01/18 19:30
S21	721	(257/E21.232 or 257/E21.035 or 257/E21.27).ccls.	US-PGPUB; USPAT; EPO; JPO; DERWENT	OR	ON	2006/01/19 14:40
S22	751	(257/E21.232 or 257/E21.035 or 257/E21.27).ccls.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/19 14:40
S23	1	semiconductor and ((dual near5 mask$4) same (amorphous near3 carbon)) and (optical)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/19 17:17
S24	5	semiconductor and ((dual near5 mask$4) same (amorphous near3 carbon))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/19 17:17
S16	13	semiconductor and ((dual near5 mask$4) with (amorphous))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/19 17:22

S25	54	semiconductor and ((dual near5 mask$4)) and (amorphous with carbon)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/19 18:41
S26	240	semiconductor and ((hard adj mask$4)) and (amorphous with carbon) and optical	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/01/19 19:01